Effect of Mass Flow Induced by a Reciprocating Rcf f ng on Electroplating. M0Fukukawa¹ and L0Tong¹ ¹Keisoku Engineering System Co., Ltd,1-9-5 Uchikanda, Chiyoda-ku, Tokyo 101-0047, Japan

Abstract

In this work, the mass flow induced by a reciprocating paddle in the electroplating cell is studied by the finite element analysis software-COMSOL Multiphysics[®]. The reciprocating movement of the paddle is simulated by using the moving mesh technique (Arbitrary Lagrangian-Eulerian: ALE method). The solution of fluid flows stirred by the paddle is coupled into the calculation of tertiary current distributions.

Numerical model

Results and discussions



Model geometry



Figure 1. Schematic of a reciprocating paddle electroplating cell

Equations

Continuity equation: $\nabla \cdot (\rho \mathbf{u}) = 0$ ρ :density

u:velocity vectorF:volume force vector

I: identity matrix

Material balance equation:

Momentum eqation: $\rho \frac{\partial u}{\partial t} + \rho \mathbf{u} \cdot \nabla \mathbf{u} = -\nabla p + \nabla \cdot \\ \left(\mu (\nabla \mathbf{u} + (\nabla \mathbf{u})^T) - \frac{2}{3} \mu (\nabla \cdot \mathbf{u}) \mathbf{I} \right) + \mathbf{F}$





$$\frac{\partial c_i}{\partial t} + \nabla \cdot \left(-D_i \nabla c_i - z_i u_{m,i} F c_i \nabla \phi_l + c_i \mathbf{u} \right) = R$$

Current density \mathbf{i}_l in the electrolyte: $\mathbf{i}_l = F \sum_{i=1}^n z_i (-D_i \nabla c_i - z_i u_{m,i} F c_i \nabla \phi_l)$

Charge balance in the electrolyte:

 $\nabla \cdot \mathbf{i}_l = Q_l$ Electroneutrality equation:

 $\Sigma z_i c_i = 0$

Tafel approximation :

$$i_{\rm loc} = -i_0 \left(\frac{C_s}{C_b}\right) \exp(-\eta/b_c)$$

Coupled computation and mesh

Numerical solutions have been obtained by using finiteelement analysis software COMSOL Multiphysics[®] 5.3. The fluid flow induced by the reciprocating movement of the paddle, mass transfer and current density distribution are fully coupled The reciprocation of paddle is simulated by the moving mesh (ale) technique.

 c_i : concentration D_i : diffusion coefficient z_i : charge number $u_{m,i}$: mobility F: Faraday's constant ϕ_l : electrolyte potential. i_0 : exchange current density c_s : surface concentration at the cathode c_b : bulk concentration b_c : Tafel slope

The results show that the reciprocating movement of the paddle can effectively increase the concentration of cupric ions and improve plated film thickness distribution at the cathode

Concluding remarks

The effect of mass flow induced by a reciprocating paddle on the electroplating has been studied in this work by coupling the solution of fluid flows with the calculation of tertiary current distributions. The finite element analysis software-COMSOL Multiphysics[®] is used. The results show that the reciprocating movement of the paddle can effectively increase the concentration of cupric ions and improve plated film thickness distribution at the cathode The present research provides an efficient method to simulate the behavior of reciprocating paddle and the application of the method would be very beneficial in studying industrial reciprocating paddle electroplating systems.



References

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